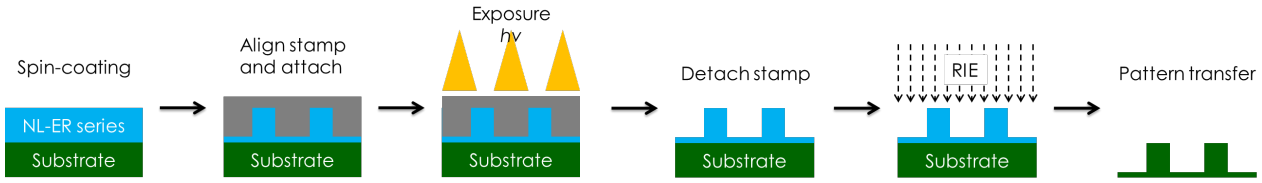
NK OPTIMER® NL series

Resists for UV-NIL (via RIE)

NL-R series

Applications

❖Nano imprint Lithography process scheme



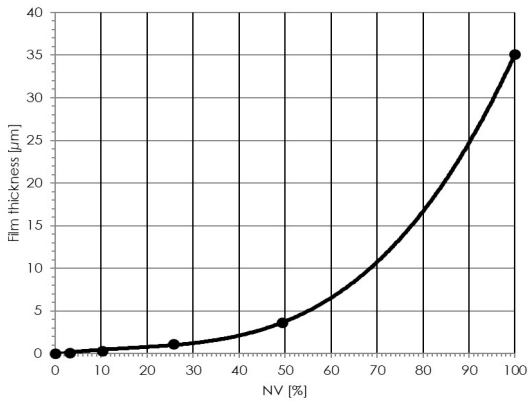
Features

❖No need for a primer treatment before coating.
❖Easily forms a thin film with superior thickness uniformity by spin coating.
❖Low volatility during vacuum defoaming on wafer.
❖Low volatility during hot-air drying on wafer.

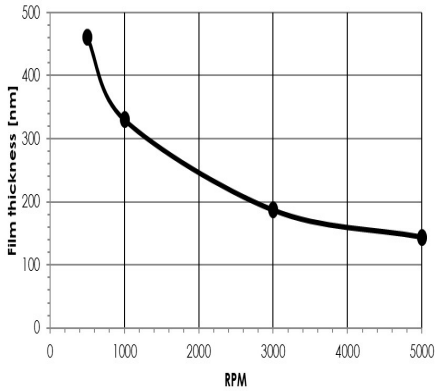
Highlighted Products

		NL-R1020	NL-R1028	NL-R1022	NL-R1030
NV		50	80	100	100
Viscosity (25˚C/77˚F) [mPa･s]		390	460	1800	1100
Etching selectivity	Al_2O_3	1.0	1.0	0.9	0.8
	TiO_2	0.6	0.6	0.5	0.5
Key Feature		Excellent film-forming ability. Excellent uniformity, Excellent decompression resistance, Excellent baking resistance	Balanced	Solvent-free, Excellent imprintability, Ideal for PDMS mold	Solvent-free, Low viscosity, Ideal for PDMS mold

NV-Thickness curve (1000RPM) (NL-R1022)



RPM-Thickness curve (NV10) (NL-R1022)



Diluent: PGMEA

Contact: Website → Contact / Request a Sample
Website: https://www.shin-nakamura.com

Wakayama : TEL +81-73(423)3256 Tokyo sales office : TEL+81- 3(3256)2671
Osaka sales office : TEL+81- 6(6533)0395 Shanghai : TEL +86-21-6235-1811
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